	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L2	89	deposition same ((electroplating adj3 time) or (anode adj3 power adj3 setting) or (anode adj3 cathode adj3 spacing) or (electroplating adj3 temperature))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/29 11:20

DOCUMENT-IDENTIFIER: US 20020100859 A1

TITLE: MOLD FOR FORMING A MICROLENS AND METHOD OF FABRICATING THE SAME

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[0074] The plated layer is formed by the **deposition** of metal ions in the electroplating bath caused by the electrochemical reaction. The thickness of the electroplated layer can be readily controlled by controlling the **electroplating time and temperature**. The following materials can be used as electroplating metal, for example. As a single metal, Ni, Au, Pt, Cr, Cu, Ag, Zn and the like can be employed. As an alloy, Cu--Zn, Sn--Co, Ni--Fe, Ni--W, Zn--Ni and the like can be used. Any material can be used so long as electroplating is possible. Ni, Cr and Cu are especially preferable as the electroplating material for the microlens mold because these metals permit a bright electroplating to be readily achieved.

US-PAT-NO: 4204136

DOCUMENT-IDENTIFIER: US 4204136 A

TITLE: Dual layer phosphor screen for cathode ray tube

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The cathode ray tube 10 of the present invention is seen in FIG. 1 and comprises a hermetically-sealed glass envelope which includes a neck portion 12, a funnel portion 14 and a faceplate portion 16. An electron gun 15 is shown in phantom disposed in the neck portion of the tube. A double level phosphor screen 18 is disposed on the interior surface of faceplate portion 16 of the cathode ray tube. A phosphor screen 18 is seen in detail in FIG. 1 wherein a first phosphor layer 20 of cataphoretically or electrophoretically deposited zinc sulphide activated by silver (P-11) phosphor is disposed upon the glass substrate. The representations of the sole FIGURE show the phosphor screen after removal of a conductive layer which is used to electrophoretically deposit the phosphor upon the glass substrate. The details of the electrodeposition process are more fully set forth in U.S. Pat. No. 3,525,679, the details of which are incorporated herein by reference. In general, it has been found desirable to deposit the cataphoretic phosphor layer 20 in a thickness which is about half that normally deposited for a standard cataphoretic screen. The phosphor utilized is a finely divided phosphor with approximately one micron average particle diameter and the phosphor layer 20 is typically about 1 to 2 microns in thickness. This very thin cataphoretic

phosphor layer 20 is provided by controlling the deposition parameters which include deposition time, anode to cathode panel spacing, solids contact with the suspension, and applied D.C. voltage. In practice, the deposition time is varied and shortened to reduce the thickness of the cataphoretic screen. As set forth in greater detail in the aforementioned prior art patent, the cataphoretically deposited screen is then baked and treated with potassium cyanide to remove the conductive film. A second gravity settled phosphor layer 22 is disposed upon the cataphoretic phosphor layer 20. The gravity settled phosphor is also a finely divided phosphor which is again zinc sulfide silver activated. A particularly effective phosphor which has been used is an aluminum oxide coated phosphor which is Lumilux Blue P11-02 available from the American Hoechst Corporation, Somerville, N.J.